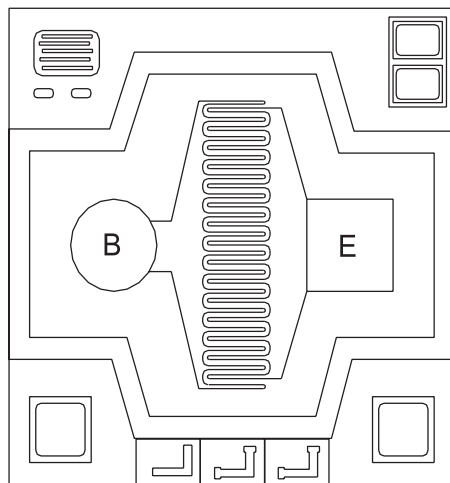


**PROCESS DETAILS**

Process	EPITAXIAL PLANAR
Die Size	21.7 x 21.7 MILS
Die Thickness	9.0 MILS
Base Bonding Pad Area	3.4 MILS DIAMETER
Emitter Bonding Pad Area	3.4 x 3.4 MILS
Top Side Metalization	Al - 10,000Å
Back Side Metalization	Au - 12,000Å

**GEOMETRY**



**BACKSIDE COLLECTOR**

R0

**GROSS DIE PER 4 INCH WAFER**

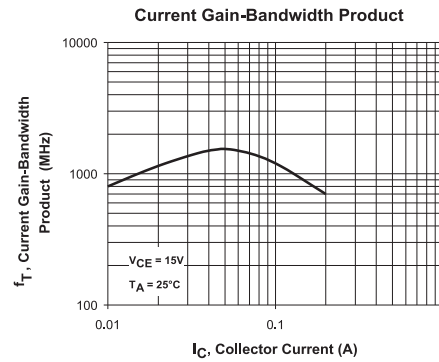
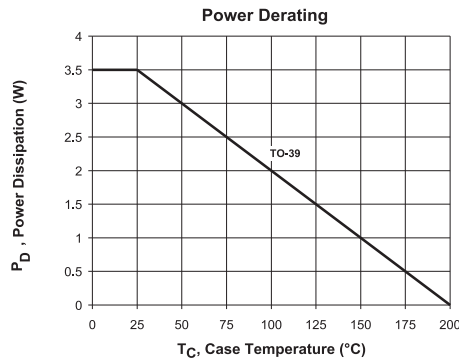
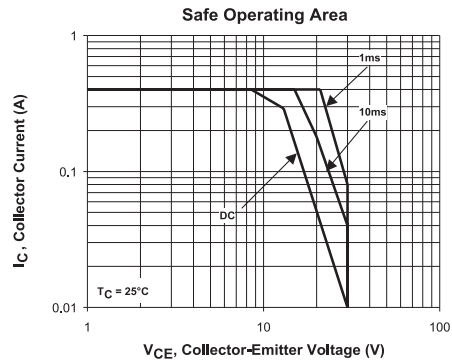
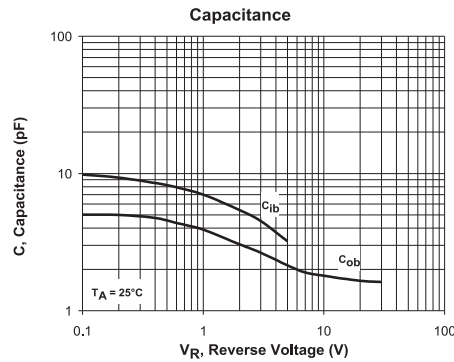
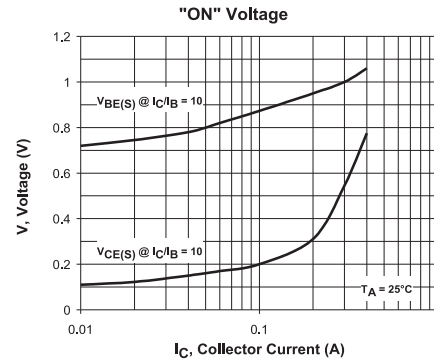
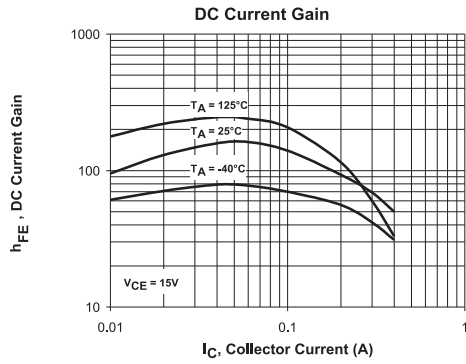
23,980

**PRINCIPAL DEVICE TYPES**

CM5943

145 Adams Avenue  
Hauppauge, NY 11788 USA  
Tel: (631) 435-1110  
Fax: (631) 435-1824  
www.centalsemi.com

R1 (1-August 2002)



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